S	earch l	Notes	

Application/Control No.	Applicant(s)/Patent under Reexamination
10/712,923	IWASA ET AL.
Examiner	Art Unit
Toan Ton	2871

	SEARCHED			
Class	Subclass	Date	Examiner	
349	137	7/29/2005	TTON	
	44,38			
	110			
	113			
	1,18			
313	503			

INTERFERENCE SEARCHED			
Class	Subclass	Date	Examiner
349	44,110,38	7/29/2005	TTON
	113,137		
313	503		
			,

SEARCH (INCLUDING SEAI)
	DATE	EXMR
EAST liquid crystal reflect\$ antireflect\$/anti reflect\$ black mask/matrix light shield\$/block\$ silicon metal\$5 gap\$	7/29/2005	TTON
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